

Notice of References Cited

Application/Control No.

10/604,651

Applicant(s)/Patent Under
Reexamination
PENG ET AL.

Examiner

Alexander G. Ghyka

Art Unit

2812

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-6,610,142	08-2003	Takayama et al.	117/8
	B	US-			
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	E	US-			
	F	US-			
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	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	JEN et al, Effects of N2O Plasma treatment... , Japanese Journal of Applied Physics, Part 2, Letter 1994
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.